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(54) Title: A METHOD AND APPARATUS FOR PRODUCING MICROCHIPS

(57) Abstract: Method for producing microchips by using immersion lithography, wherein the immersion fluid comprises an additive so that the refractive index of the immersion fluid is increased relative to the fluid not comprising the additive. The exposure light in the method has improved resolution, so that microchips having an increased integration density are obtained. The invention also relates to the immersion fluid and an apparatus for immersion lithography, comprising the immersion fluid.

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